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A. Andrieux, N. Dorval, F. Fossard, L. Schué, P. Lavenus, et al.. CVD synthesis and characterization of hexagonal boron nitride thin films. 18th International Microscopy Congress, Sep 2014, PRAGUE, Czech Republic. hal-01111569

HAL Id: hal-01111569

https://hal.science/hal-01111569

Submitted on 30 Jan 2015

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# CVD SYNTHESIS AND CHARACTERIZATION OF HEXAGONAL BORON NITRIDE THIN FILMS

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As a typical two-dimensional material, graphene has attracted great interest due to its remarkable optical, mechanical and electronic properties. It has been demonstrated that substrates supporting graphene have a high impact on its electronic properties, especially on its electron mobility [1]. Hexagonal boron nitride (h-BN), as a graphene analogue, seems to be an excellent candidate to serve as a graphene substrate. Indeed, this layered material, made of a stacking of planar BN hexagonal networks, is a semiconductor with a large band- gap (~ 6 eV) and with an atomically smooth surface [2]. It has been confirmed that the on- substrate mobility of graphene is preserved on h-BN and is very close to that of suspended graphene [3]. As a consequence, h-BN could be useful as a complementary two-dimensional dielectric substrate for high-performance graphene electronics. However, synthesis of highquality and large-area h-BN with controllable number of layers remains a great challenge and thus the implementation of h-BN/graphene hybrid structures is still limited.

In this context, our goal is to optimize an ONERA made LPCVD installation suited to the synthesis of h-BN films to be able to obtain graphene and ultra thin film of h-BN, less than 10 nm thick, uniform, with high quality and smooth surface. Here, we report the first results on the growth of h-BN on nickel substrate under our LPCVD method, using borazine ( $B_3N_3H_6$ ) as precursor. In order to further characterize the grown h-BN layers, a direct method was used to transfer them from

their growth substrate onto a carbon-coated gold TEM grid [4]. HRTEM (ARM 200 CF) and Fast Fourier Transform (FFT) were used to probe the structure and crystallinity of our sample. Electron energy loss spectroscopy (EELS) performed on a monochromated Libra 200 was used to determine the chemical composition and valence states of the h-BN film.

Additionnal Raman spectroscopy was performed in order to have macroscopic measurements on the structural quality of our hBN.

Only a few Raman modes are active in h-BN. The main mode is the E<sub>2G</sub> mode at 1367 cm<sup>-1</sup> and its FWHM gives a good idea of the crystalline quality. In this paper, we present h-BN exhibiting a narrow peak (13 to 20 cm<sup>-1</sup>) close to other "state of the art" CVD h-BN (11cm<sup>-1</sup>).

[1] A.K. Geim, K.S. Noselov. Nat. Mater. 2007, 6, 183-191.

[2] K.H. Lee, H.J. Shin, J. Lee, I. Lee, G.H. Kim, J.Y. Choi, S.W. Kim. *Nano Lett.* **2012**, 12, 714–718.

[3] C.R. Dean, A.F. Young, I. Meric, C. Lee, L. Wang, S. Sorgenfrei, K. Watanabe, T. Taniguchi, P. Kim, K.L. Shepard, J. Hone. *Nat. Nanotechnol.* **2010**, 5, 722–726.

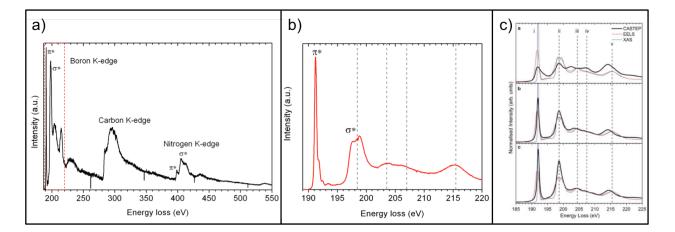
[4] W. Regan, N. Alem, B. Alemán, B. Geng, C. Girit, L. Maserati, F. Wang, M. Crommie, A. Zettl, *Appl. Phys. Lett.* **2010**, 96, 113102.

### Acknowledgement

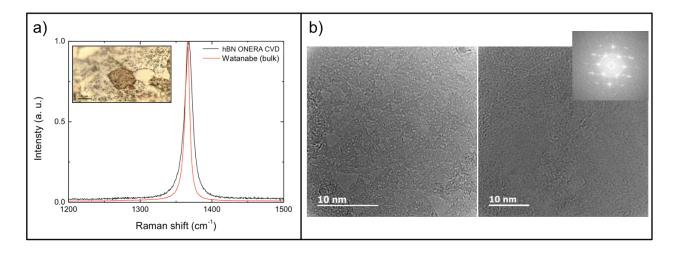
### **Flagship**

Authors want to thank Jean-Claude Daux, Jean-François Justin, Bruno Passily for their technical assistance in the CVD synthesis. Financial support PRF
Raman: Ingrid Stenger GEMAC, Université Versailles St Quentin – CNRS, 45 avenue des Etats Unis, Versailles, France

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- a) EELS spectrum of ONERA CVD hBN film.
- b)EELS spectrum of the B K-edge of ONERA CVD hBN film.
- c)The calculated B K-edge for AB configuration compared with EELS and XAS experimental spectra [McDougall et al. Microsc.Microanal. 2014]



- a) Raman spectrum of ONERA CVD hBN film on nickel substrate
- b) High resolution TEM images of ONERA CVD hBN film

The corresponding FFT showing a set of hexagonal patterns from hBN film